

## IN THE CLAIMS:

Please amend the claims as follows:

- 1.(Currently Amended) A chemical-mechanical polishing composition, comprising:  
an aqueous solution; and  
an abrasive comprising polymeric particles, wherein the polymeric particles would in a dried state have an electric charge, and wherein the polymeric particles in the aqueous solution have an ~~having an~~ electrical charge sufficient to create an electrostatic repulsive force between proximate particles.
- 2.(Previously presented) The composition of claim 1, wherein the particles comprise a material selected from a group consisting of a polyacrylate, a polyvinyl alcohol, a polyvinyl benzene, a polyvinylidene chloride, a polymelamine, a polypropylene, a polyethylene, a polystyrene, a polyester, a polyamide, a polyurethane, and any combination thereof.
3. (Previously presented) The composition of claim 1, wherein the particles comprise a material selected from polymethyl methacrylate and polybutyl methacrylate.
4. (Previously presented) The composition of claim 1, wherein the particles have a functionality selected from a group consisting of hydrophilicity and hydrophobicity.
5. (Previously presented) The composition of claim 1, wherein an average diameter of the particles is from about 0.1 to about 1.8 microns.
6. (Previously presented) The composition of claim 1, further comprising an oxidizing agent.
- 7.(Previously presented) The composition of claim 1, further comprising an oxidizing agent selected from a group consisting of hydroxylamine, a salt of hydroxylamine, hydrogen peroxide, periodic acid, a peracetic acid, ammonium persulfate, and any combination thereof.
- 8.(Previously presented) The composition of claim 1, further comprising an oxidizing agent that comprises hydroxylamine nitrate.

9.(Previously presented) The composition of claim 7, further comprising a secondary oxidizing agent selected from a group consisting of a salt of iron, copper, or cesium, a chelated complex of any such salt, nitric acid, and any combination thereof.

10.(Previously presented) The composition of claim 1, wherein the composition has a zeta potential of from about -60 mV to about 10 mV.

11.(Cancelled)

12.(Previously presented) The composition of claim 1, wherein the composition has a pH of from about 4 to about 8.

13.(Previously presented) The composition of claim 1, wherein the composition has a pH of from about 5 to about 7.

14.(Currently Amended) The composition of claim 1, wherein the aqueous solution further comprises ionic species.

15.(Currently Amended) A chemical-mechanical polishing composition,  
comprising: an aqueous solution;  
an abrasive comprising polymeric particles selected from a group consisting of a polyacrylate, a polyvinyl alcohol, a polyvinyl benzene, a polyvinylidene chloride, a polymelamine, a polypropylene, a polyethylene, a polystyrene, a polyester, a polyamide, a polyurethane, and any combination thereof, wherein the polymer particles are electrified and the polymer particles in said aqueous solution have having an electrical charge sufficient to create an electrostatic repulsive force between adjacent particles; and  
an oxidizing agent selected from a group consisting of hydroxylamine, a salt of hydroxylamine, hydrogen peroxide, periodic acid, a peracetic acid, ammonium persulfate, and any combination thereof.

16.(Previously presented) The composition of claim 15, wherein the particles

comprise a material selected from polymethyl methacrylate and polybutyl methacrylate.

17.(Previously presented) The composition of claim 15, wherein the particles have a functionality selected from a group consisting of hydrophilicity and hydrophobicity.

18.(Previously presented) The composition of claim 15, wherein an average diameter of the particles is from about 0.1 to about 1.8 microns.

19.(Previously presented) The composition of claim 15, wherein the oxidizing agent comprises hydroxylamine nitrate.

20.(Previously presented) The composition of claim 15, further comprising a secondary oxidizing agent selected from a group consisting of a salt of iron, copper, or cesium, a chelated complex of any such salt, nitric acid, and any combination thereof.

21.(Cancelled)

22.(Cancelled)

23.(Previously presented) The composition of claim 15, wherein the composition has a pH of from about 4 to about 8.

24.(Previously presented) The composition of claim 15, wherein the composition has a pH of from about 5 to about 7.

25.(Currently Amended) The composition of claim 15, wherein the aqueous solution further comprises ionic species.

26.(Previously presented) A method of polishing a substrate surface using a polishing pad, comprising:

providing the composition of any of claims 1, 6, and 15, on the surface; and causing relative motion between the surface and the polishing pad.

27.(Previously presented) The method of claim 26, wherein the surface comprises a feature of a material selected from a group consisting of aluminum, copper, silver, tungsten, any alloy of thereof, and any combination thereof.

28.(Previously presented) A method of preparing a composition for chemical-mechanical polishing, comprising:

- providing an aqueous solution;
- imparting an electrostatic charge to polymeric particles, the electrical charge sufficient to create an electrostatic repulsive force between proximate particles; and adding an abrasive comprising the electrostatically charged polymeric particles to the aqueous solution.

29.(Previously presented) A method of preparing a composition for chemical-mechanical polishing, comprising:

- providing an aqueous solution;
- imparting an electrostatic charge to polymeric particles, the electrical charge sufficient to create an electrostatic repulsive force between proximate particles;
- adding an abrasive comprising the electrostatically charged polymeric particles to the aqueous solution; and
- adding an oxidizing agent to the aqueous solution.

30.(Previously presented) The method of claim 28 or 29, further comprising adjusting a pH of the composition.

31.(Previously presented) A composition for chemical-mechanical polishing produced according a method of claim 28 or 29.

32.(New) The composition of claim 15, wherein the particles were electrified by passing through an electricstatic field, by friction electrification, or by contact with an electrified surface.

33.(New) The composition of claim 15, wherein the polymer particles have a water

content of about 2% or less.

34.(New) The composition of claim 1, wherein the electric charge the polymeric particles would have in a dried state is the same sign as the charge imparted by the ionization of polar groups in the particles when the particles are in the aqueous solution.